



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:
David S. Pecora

Serial No.: 09/854,206

Filed: May 11, 2001

For: **ETCH OF SILICON NITRIDE SELECTIVE TO
SILICON AND SILICON DIOXIDE USEFUL
DURING THE FORMATION OF A
SEMICONDUCTOR DEVICE**

§
§ Group Art Unit: 1765
§
§ Examiner: Binh X. Tran
§
§ Atty. Docket: 00-0737.00/US
§
§ Paper No. 6
§
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Washington, D.C. 20231

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on or before the date below:

January 21, 2003

Date

Kevin D. Martin
Signature

**PETITION FOR EXTENSION OF TIME
FOR THE OFFICE ACTION OF AUGUST 19, 2002**

Applicant hereby petitions to extend the period for response to the Outstanding Office Action mailed August 19, 2002 for two (2) months, from November 19, 2002 to January 19, 2003. Because January 19, 2003 falls on a Sunday, and Monday, January 20, 2003 is a Federal Holiday within the District of Columbia, the date is extended to Tuesday, January 21, 2003.

Accordingly, the Commissioner is requested to charge the requisite late fee under 37 CFR 1.17(a)(2), which is believed to be \$410.00, and any additional fee which may be required to Micron Technology, Inc. Deposit Account 13-3092, Order No. 00-0737.00. A duplicate copy of this petition is enclosed.

Respectfully submitted,

Kevin D. Martin
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